



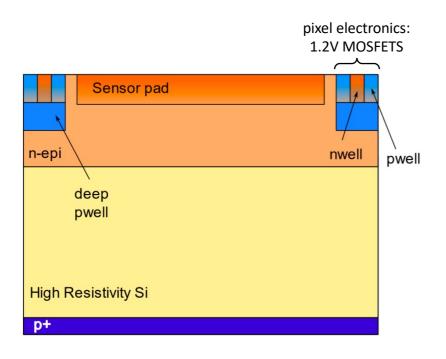
Marco Mandurrino, on behalf of the ARCADIA Collaboration marco.mandurrino@to.infn.it 2024 European Edition of the International Workshop on the Circular Electron-Positron Collider

Apr 8–11, 2024 - Marseille, France

# The ARCADIA sensor concept



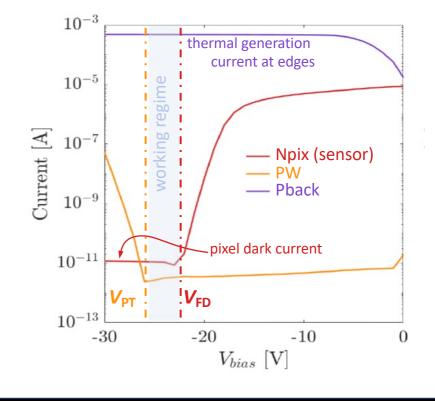
#### **Fully-depleted Monolithic Active Pixel Sensors**



- n-type high resistivity substrate with n-type epitaxial active volume
- 110 nm CMOS process (LFoundry)
- deep-p-wells shielding n-wells with electronics
- reverse-biased junction: depletion grows from back to top

#### Main constraints:

- full-depletion condition
- edge breakdown induced by the topside voltage
- punch-through due to the backside bias



# The ARCADIA sensor concept



#### Substrates and post-processing

Type 1:

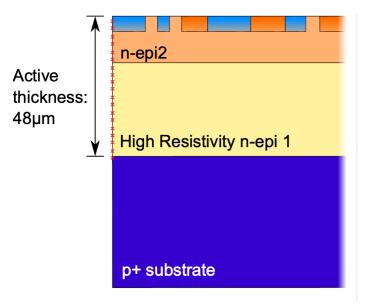
thinning to 100 or 300 µm total thickness

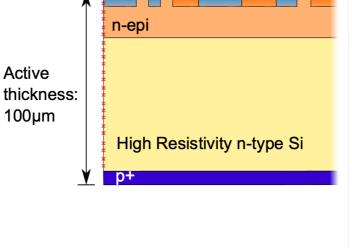
#### Type 2:

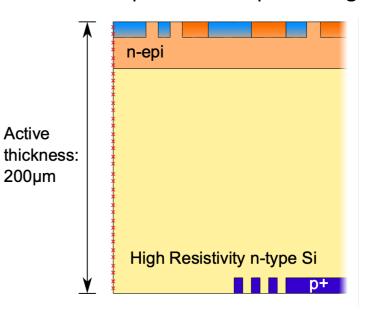
thinning, backside **p**<sup>+</sup> **implantation** and laser
annealing

#### Type 3:

thinning, **lithography**, backside **p**<sup>+</sup> **implantation** and laser annealing, **insulators/metal** deposition and patterning

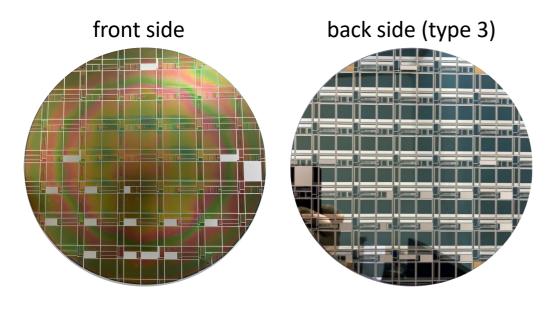








#### 8" wafers

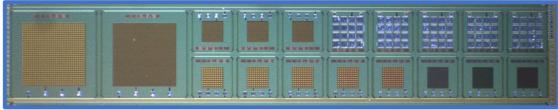


#### Structures:

- ightharpoonup small **pixel arrays** with **different pitch** (10 μm 25 μm 50 μm) with and w/o active readout
- ► strip detectors with and w/o active readout
- passive test structures for sensors characterization and process qualification
- ► Main Demonstrator: 25-μm-pitch pixel sensor, 512 × 512 array



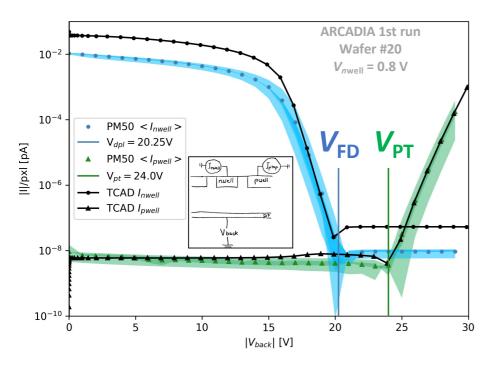
ARCADIA
Main Demonstrator



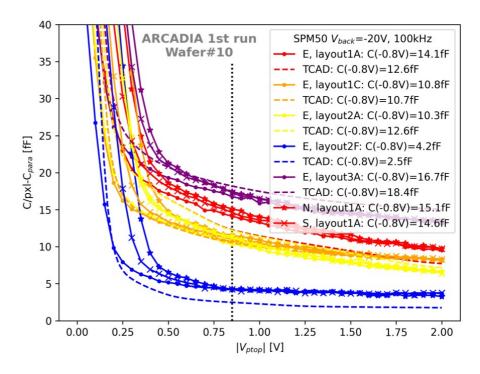
passive test structures block



#### **Electrical characterizations**



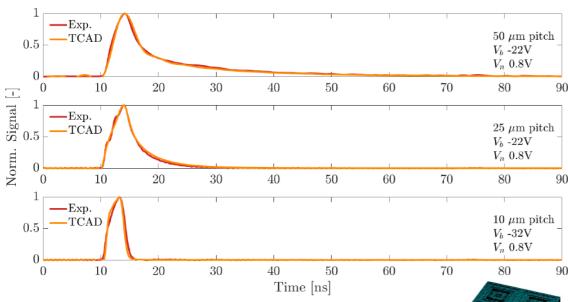
- different pixel layouts have been tested
- intra- and inter-wafer uniformity evaluated
- ▶ TCAD parameters adjusted on experimental results



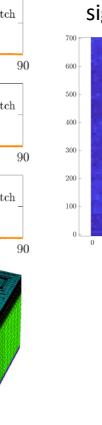
capacitance dominated by the sensor perimeter

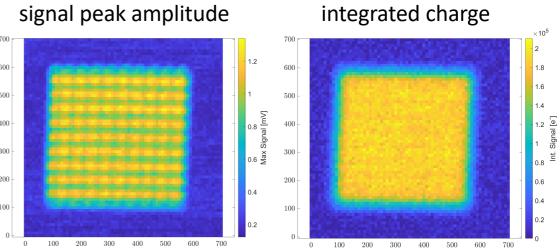


#### Dynamic response with laser



- < 100 ps FWHM IR laser pulse</p>
- passive pixel array test structures
- 100 μm active thickness
- different pixel pitch: 50 μm 25 μm 10 μm

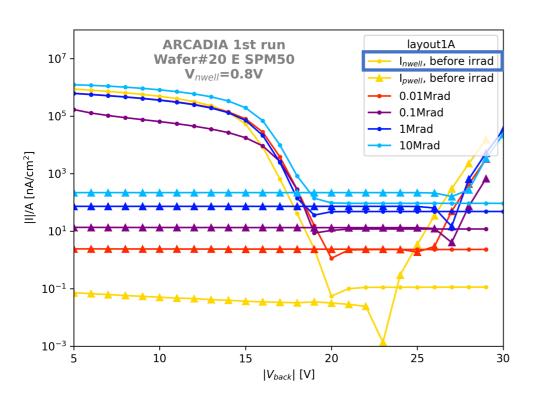


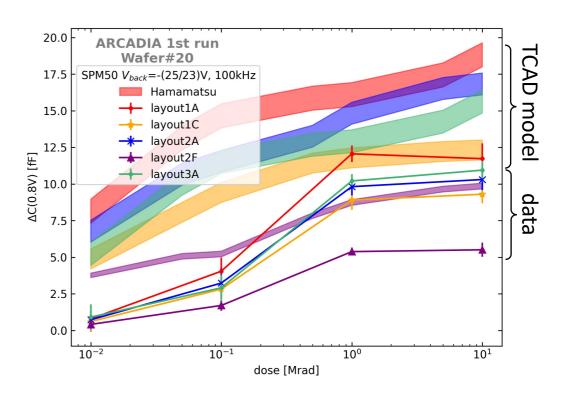


- ▶ 10 μm FWHM focused IR laser
- 50-μm-pitch test structure
- $ightharpoonup V_{\text{top}} = 0.8 \text{ V} \text{ and } V_{\text{back}} = -22 \text{ V}$
- ightharpoonup 10 µm steps in X and Y directions



Pixel radiation hardness: X-rays @ University of Padova, Italy

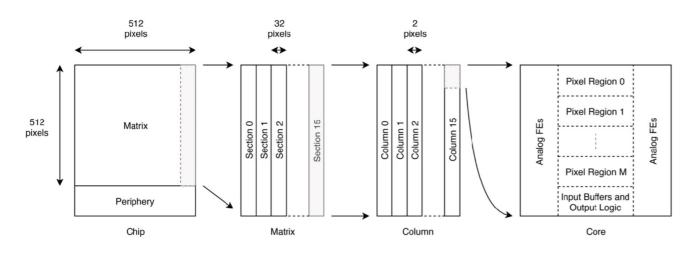




- increase of pixel leakage current with Total Ionizing Dose (TID) due to surface generation
- □ capacitance post-irradiation overestimated by the Perugia model with Hamamatsu parametrization



#### Main Demonstrator - architecture



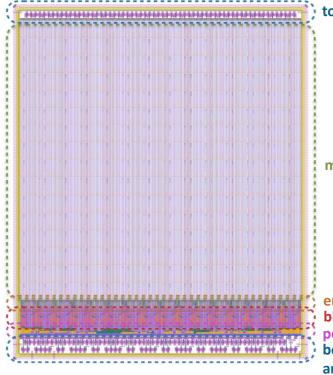
Pixel pitch: 25 μm

► Electronics: analog and digital, with in-pixel threshold and data storage

► Architecture: **event-driven**, with active pixels sending their address to the chip peripheral circuits

⊳ (Low) power: 20 mW/cm²

► (High) event rate: 100 MHz/cm²



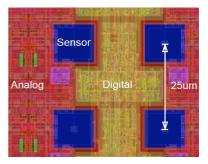
top padframe (auxiliary supply)

matrix

end of sector (reads & configure) biasing periphery bottom padframe (stacked power

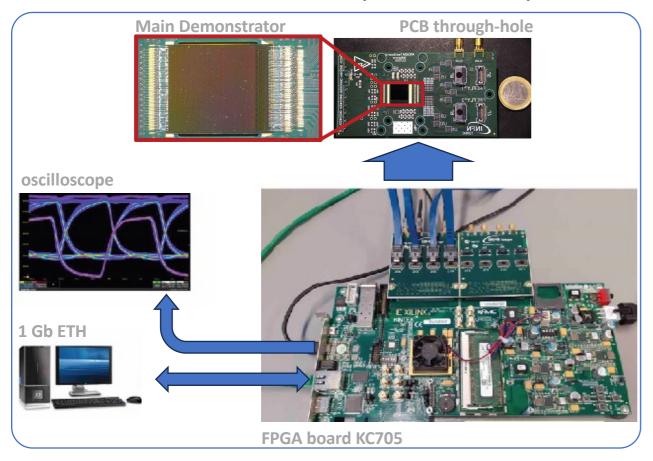
and signal pads)



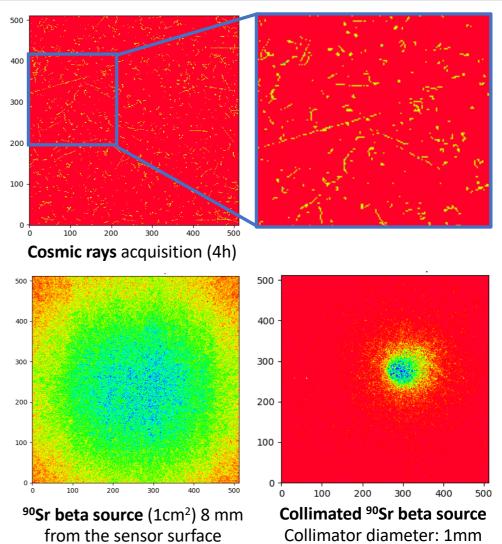




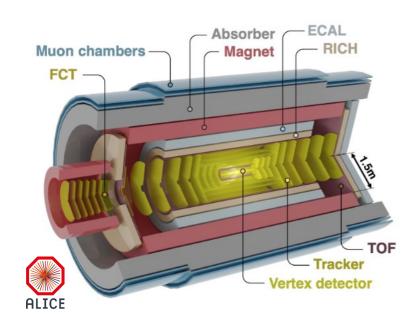
#### Main Demonstrator - acquisition setup



- ► Total **power consumption**: **10 mW/cm²** at low event rates
- **Design specification**: **20 mW/cm²** at rates up to 100 Mevents/cm²

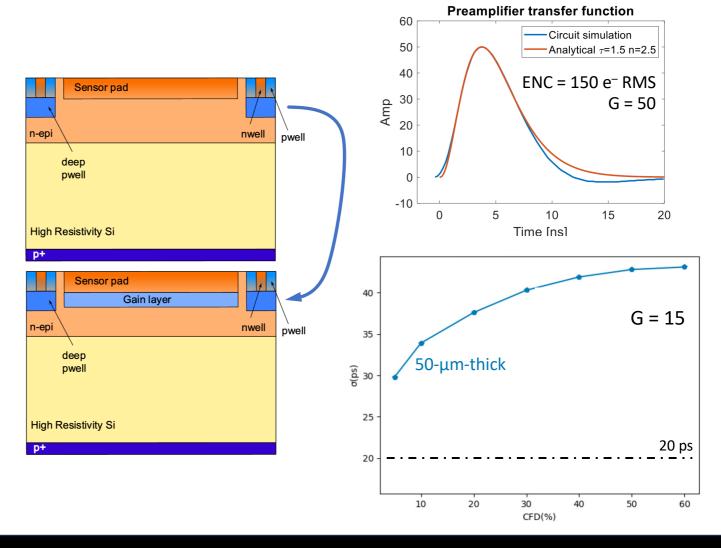




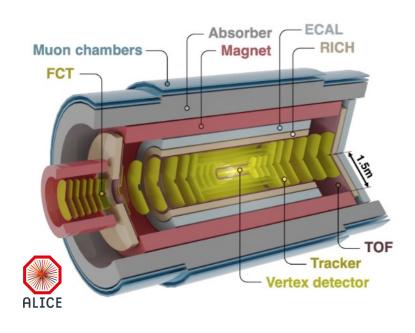


#### ALICE 3 **TOF** detector:

- ightharpoonup particle ID with low  $p_T$  ⇒  $\sigma_t$  ~ 20 ps

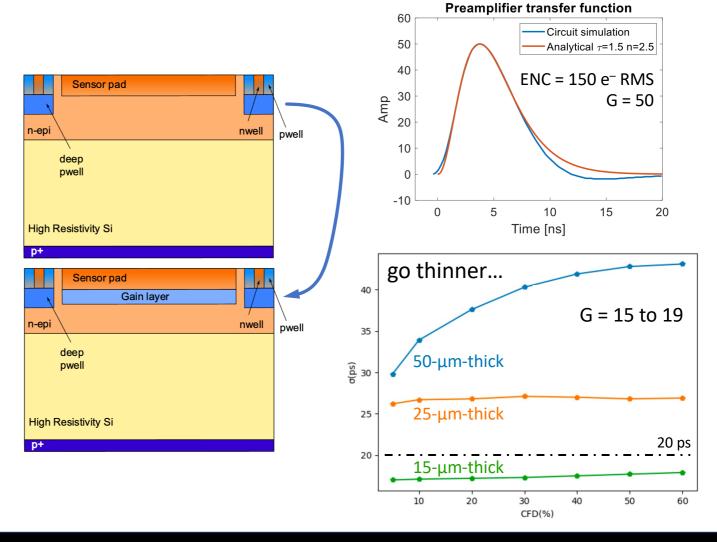






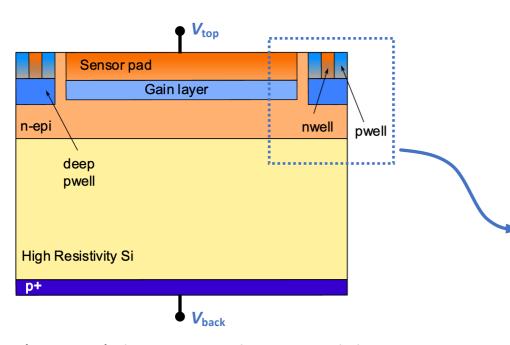
#### ALICE 3 **TOF** detector:

- ▶ high-resolution tracking and vertexing
- ightharpoonup particle ID with low  $p_T$  ⇒  $\sigma_t$  ~ 20 ps



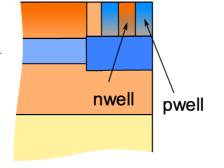


Sensor structure and layout



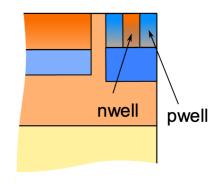
#### **Layout A1:**

deep-p-wells are in connection with the p-gain implant ⇒ more uniform charge multiplication



#### **Layout A2:**

standard solution: **direct path** to the  $n^+$  collection
electrode  $\Rightarrow$  more **uniform time response**; NO multiplication of charges at
borders



 $V_{\text{top}}$  (30-40 V) determines the gain, while  $V_{\text{back}}$  (-30 V) defines the drift field in the substrate

top voltage limited by edge breakdown backplane bias limited by punch-through

- ▶ four gain dose splittings to cope with implantation uncertainties
- target: gain in the range 10 − 30
- ► 50, 100 and 200 μm active thicknesses



#### MadPix: first small-scale (4 × 16 mm²) demonstrator with gain and integrated electronics

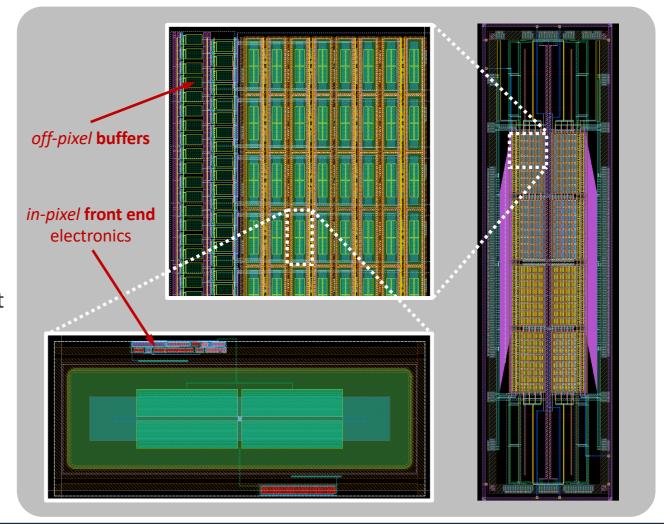
- ▶ 8 matrices (64 pixel pads each) implementing different sensor and front-end flavours
- ightharpoonup pads of 250 × 100  $\mu m^2$
- readout: **64 × 2 analog outputs** on each side
- **rolling shutter** of single matrix readout

#### **Front-end** (in-pixel)

- ▶ Cascoded common source amplifier, followed by a differential buffer (1.2V)
- ► AC-coupled with sensor (in order to decouple it from the sensor top voltage)
- ▶ Power consumption: 0.18 mW/ch

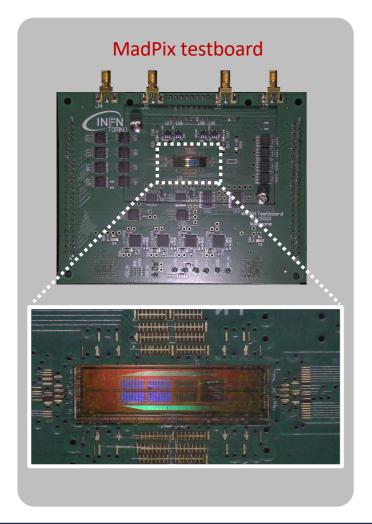
#### **Source follower** *off-pixel* buffers (3.3V)

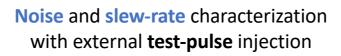
- ▶ AC-coupled with FE
- ▶ Power consumption: 1.65 mW/ch

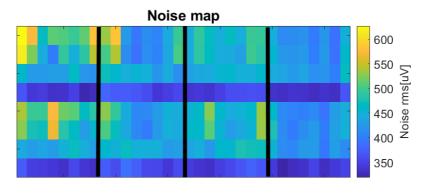


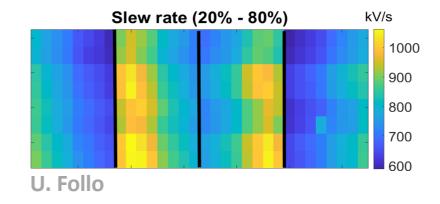


#### MadPix: first small-scale (4 × 16 mm²) demonstrator with gain and integrated electronics

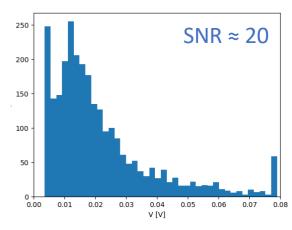


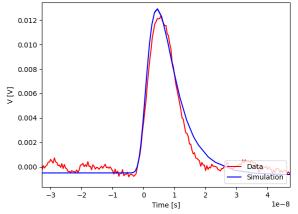






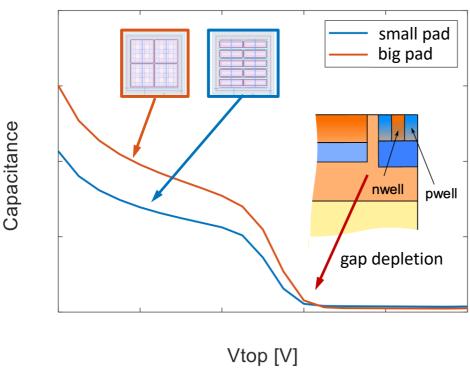
#### First data with **beta source** (90**Sr**)

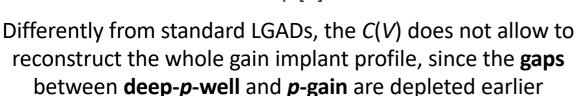


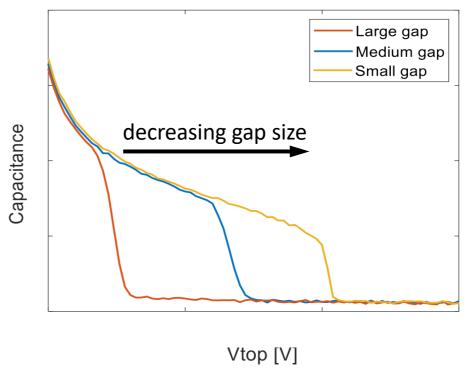




#### Electrical characterization – standalone passive test-structures



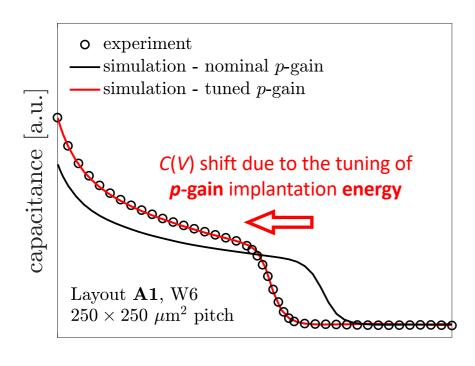




The **foot/knee** observed in the C(V) curves depends on the **size** of the gap. A **larger gaps** are fully **depleted** at **lower voltage** 

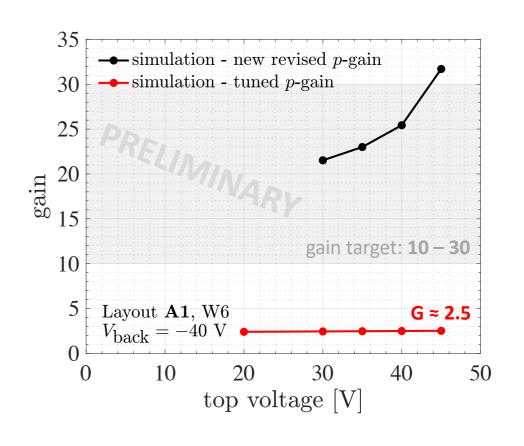


Investigations about the gain (target: 10 - 30)



top voltage [a.u.]

the **p**-gain implant energy must be reduced by ~30% to recover the mismatch

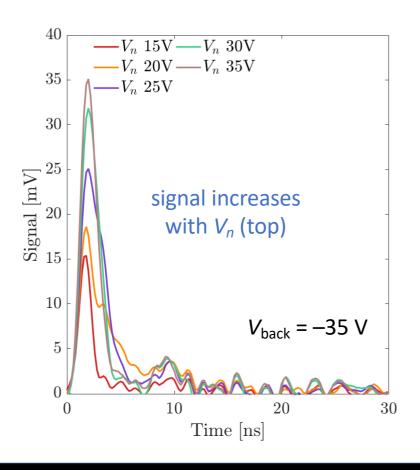


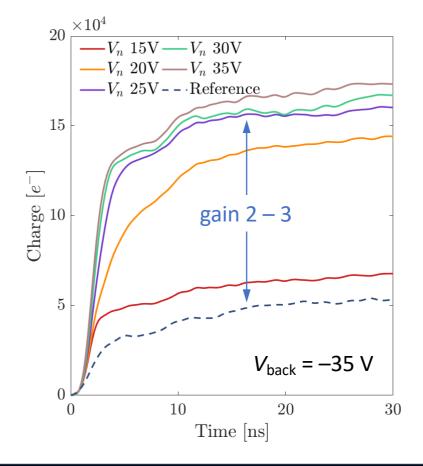


#### Dynamic characterization – standalone passive test-structures

Focused IR laser spot ( $\sim$ 10  $\mu$ m)

Backside illumination





### Conclusions

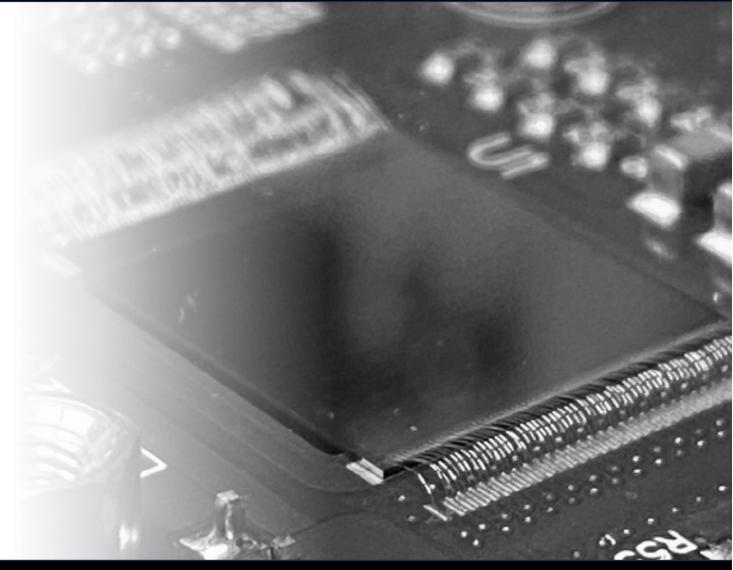


- ▶ We proved the compatibility between the LGAD technology and the 110-nm CMOS process, thanks to the 3rd ARCADIA production
- ► This engineering run has been characterized through static and dynamic laboratory tests, as well as numerical simulations, allowing to find the p-gain implantation error
- ... what's next?
- Laboratory characterizations of the incoming short-loop run as a testbench for next test beams
- □ Optimize the sensor in view of timing applications (improvement of periphery layout, new substrates, pad area / active thickness ratio, ...)
- ▶ New sensor concepts on the way: follow our next contributions (e.g. Pisa Meeting)



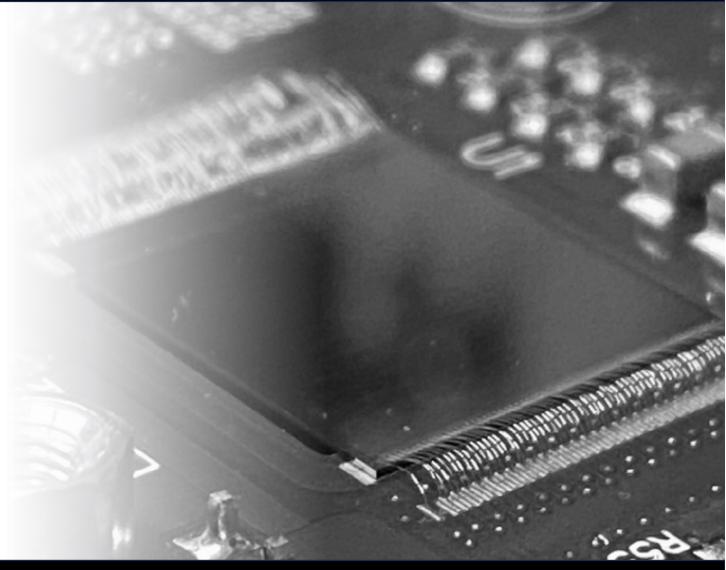
# Thank you for the attention!







# backup





#### Pixel characterization

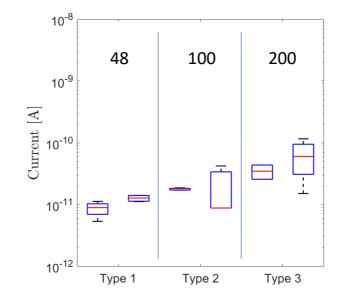
#### static characteristics

Active thickness (μm)	48	100	200
bias voltage (V)	25	20-35	60-100
dark current density (pA/cm²)	100-350	230 - 500	650 - 2000

#### dynamic characteristics

Pixel pitch (μm) @ 100-μm-thick	10	25	50
capacitance (fF)	1.9	3	12.7
time for 90% charge collection with picosecond IR laser (ns)	4	10	31

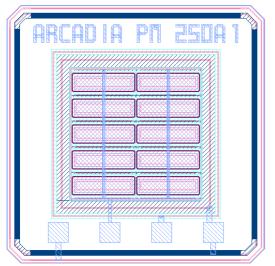
dark currents in
1.5 mm × 1.5 mm
pixel arrays with
different active
thicknesses



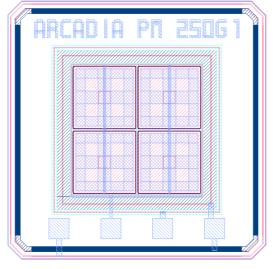


#### Electrical characterization – standalone passive test-structures

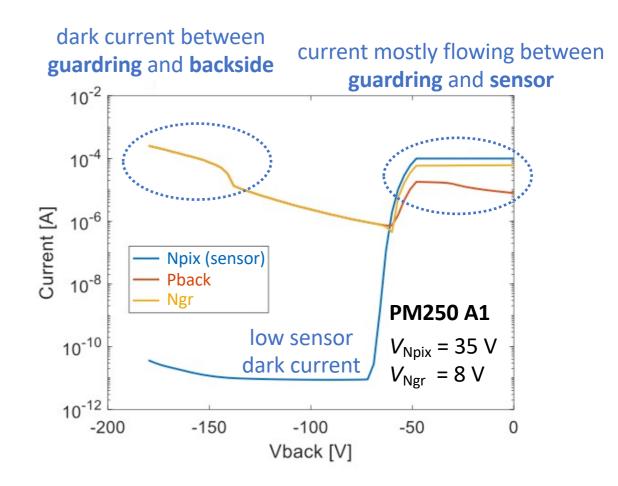
Designed for test at the probe station and with external amplifiers



Rectangular passive pads:  $70 \mu m \times 250 \mu m$ 

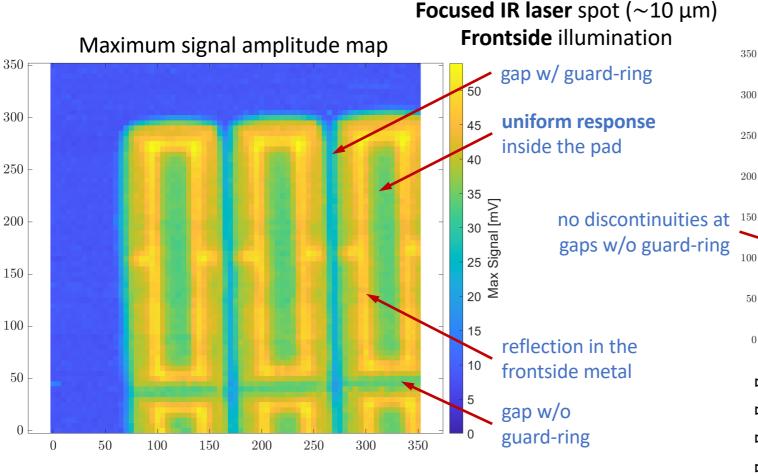


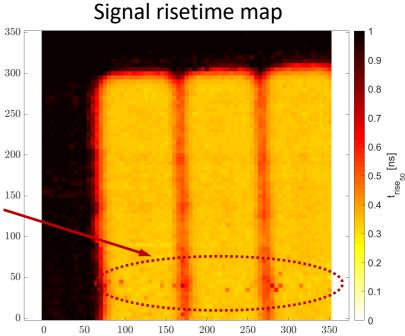
Square passive pads with large fill-factor:  $250 \mu m \times 250 \mu m$ 





#### Dynamic characterization – standalone passive test-structures



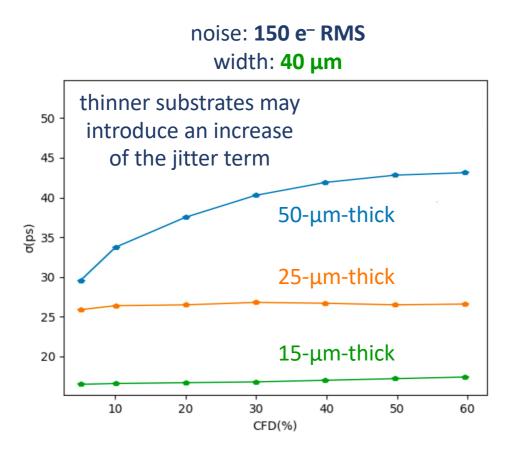


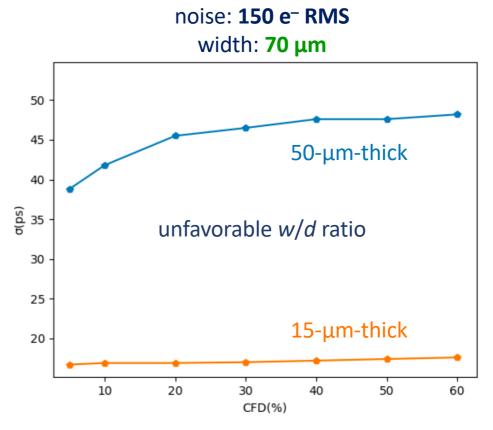
- ightharpoonup 70 × 250 μm<sup>2</sup>**PM250 A1**array
- $ightharpoonup V_{\text{pix}} = 40 \text{ V}, V_{\text{back}} = -35 \text{ V}$
- Focused laser spot (~10 μm)
- > 5 μm motor step

# $\sigma_t$ simulations with MC



#### Time resolution vs. sensor width

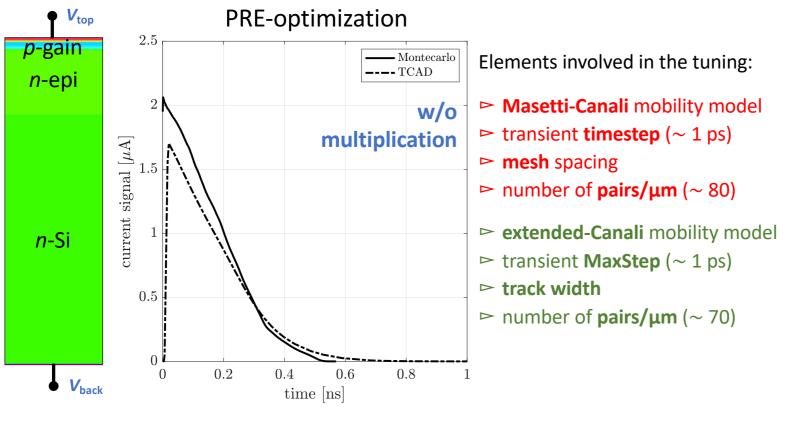


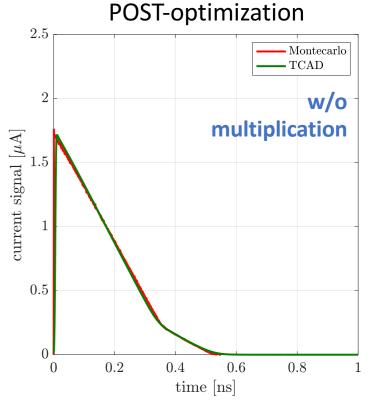


## **Optimization of simulation tools**



Signal simulations w/ and w/o default models (and parameters) for **TCAD** and **Montecarlo** 





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Signal simulations w/ and w/o default models (and parameters) for **TCAD** and **Montecarlo** 

